

L Number	Hits	Search Text	DB	Time stamp
1	5	645736.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/03 09:44
2	2	5645736.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/03 09:48
4	5	(anion\$4 near3 polyelectro\$5) same polish\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/03 09:50
5	26	poly\$2arcylic near4 acid	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/03 09:50
6	0	(poly\$2arcylic near4 acid) and (polish\$4 or cmp)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/03 10:07
8	20	polyethylenimine same (polish\$4 or cmp)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/03 10:09
15	37	(silicon adj nitride or sin) near10 (silicon adj oxide or silicon adj dioxide or sio2 or "sio.sub.2") near10 trench\$4 near10 (planar\$4 or polish\$) and @py<2000	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/03 11:45
16	2	6110396.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/03 11:51
19	38	(aluminum or tungsten) near10 (silicon adj dioxide) same planar\$ same polish\$ and @py<2000	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/03 11:54
20	10	(aluminum or tungsten) near10 (silicon adj dioxide) same trench\$ same polish\$ and @py<2000	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/03 14:20
21	7	(aluminum or tungsten) near10 (silicon adj dioxide and silicon adj nitride) same trench\$ same polish\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/03 14:25
23	95	((aluminum or tungsten) near10 (silicon adj dioxide or silicon adj nitride) same planar\$ same polish\$) and @py<2001	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/03 14:26
24	52	((aluminum or tungsten) near10 (silicon adj dioxide or silicon adj nitride) same planar\$ same polish\$) and @py<2000	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/03 14:26